

## (12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property  
Organization  
International Bureau



(43) International Publication Date  
18 November 2004 (18.11.2004)

PCT

(10) International Publication Number  
**WO 2004/100622 A1**

(51) International Patent Classification<sup>7</sup>: **H05H 1/18**

Villa, Haengdang-dong, Seongdong-gu, Seoul 133-070 (KR). LEE, Myoung-Jae [KR/KR]; 113-1303 Parktown, Sunae-dong, Bundang-gu, Seongnam-city, Kyungki-do 463-020 (KR).

(21) International Application Number:  
PCT/KR2004/000962

(22) International Filing Date: 26 April 2004 (26.04.2004)

(74) Agent: LEE, Young-Pil; The Cheonghwa Bldg. 1571-18 Seocho-dong,, Seocho-gu, Seoul 137-874 (KR).

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:  
10-2003-0029360 9 May 2003 (09.05.2003) KR

(71) Applicant (for all designated States except US):  
**HANYANG HAK WON CO. LTD.** [KR/KR]; 17 Haengdang1-dong, Seongdong-gu, Seoul 133-791 (KR).

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

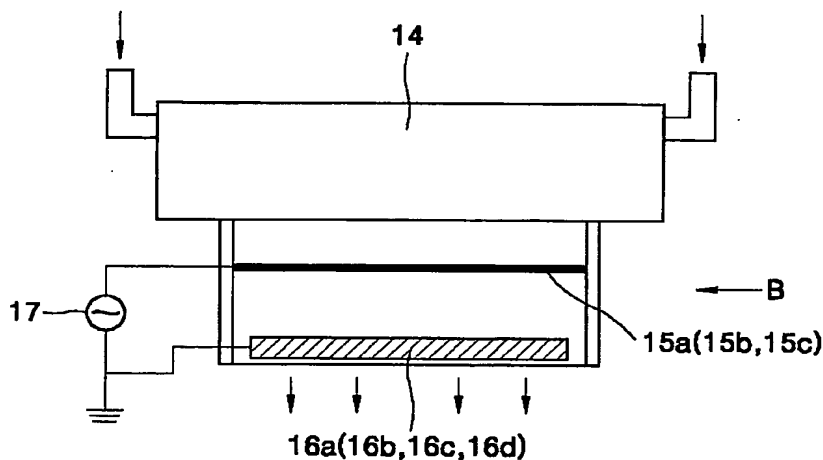
(72) Inventors; and

(75) Inventors/Applicants (for US only): **CHUNG, Kyu-Sun** [KR/KR]; Dept. of Nuclear Engineering, Hanyang University 17 Haengdang1-dong, Seongdong-gu, Seoul 133-791 (KR). **CHOI, Yong-Sup** [KR/KR]; Rm. 201 Donga

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI,

[Continued on next page]

(54) Title: APPARATUS FOR INJECTING PLASMA GAS IN ATMOSPHERE



(57) Abstract: An apparatus for injecting plasma in the atmosphere is provided, including a plurality of dielectric panels (13a, 13b, 13c, and 13d), which are disposed in parallel at predetermined intervals, a gas supply portion (14), to which the dielectric panels (13a, 13b, 13c, and 13d) are fixed and which supplies a gas to spaces between the dielectric panels (13a and 13b), between the dielectric panels (13b and 13c), and between the dielectric panels (13c and 13d), power electrodes (15a, 15b, and 15c), which are linearly installed near the gas supply portion (14) and between the dielectric panels (13a and 13b, between the dielectric panels 13b and 13c, and between the dielectric panels 13c and 13d), respectively, ground electrodes (16a, 16b, 16c, and 16d), which are formed in the ends of the dielectric panels (13a, 13b, 13c, and 13d), respectively, and a high frequency generator (17), which applies high frequency power to the power electrodes (15a, 15b, and 15c) and the ground electrodes (16a, 16b, 16c, and 16d).

WO 2004/100622 A1



SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

*For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.*

**Published:**

— with international search report



The present invention provides an atmospheric plasma injecting apparatus which can generate plasma by using less power and effectively inject the plasma into the outside.

The atmospheric plasma injecting apparatus comprises a plurality of dielectric panels 13a, 13b, 13c, and 13d, a gas supply portion 14, power electrodes 15a, 15b, and 15c, ground electrodes 16a, 16b, 16c, and 16d, and a high frequency generator 17. The dielectric panels 13a, 13b, 13c, and 13d are disposed in parallel at predetermined intervals. The dielectric panels 13a, 13b, 13c, and 13d are fixed to the gas supply portion 14, which supplies a gas to spaces between the dielectric panels 13a and 13b, between the dielectric panels 13b and 13c, and between the dielectric panels 13c and 13d. The power electrodes 15a, 15b, and 15c are linearly installed near the gas supply portion 14 and between the dielectric panels 13a and 13b, between the dielectric panels 13b and 13c, and between the dielectric panels 13c and 13d, respectively. The ground electrodes 16a, 16b, 16c, and 16d are formed in the ends of the dielectric panels 13a, 13b, 13c, and 13d, respectively. The high frequency generator 17 applies high frequency power to the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d.

#### Brief Description of the Drawings

FIG. 1 is a front view of a conventional apparatus for injecting plasma in the atmosphere;

FIG. 2 shows the apparatus of FIG. 1 viewed from direction A;

FIG. 3 is a front view of an apparatus for injecting plasma in the atmosphere according to the present invention; and

FIG. 4 shows the apparatus of FIG. 3 viewed from direction B.

#### Best mode for carrying out the Invention

An apparatus for injecting plasma in the atmosphere according to the present invention will now be described in detail with reference to the attached drawings.

Referring to FIGS. 3 and 4, an apparatus for injecting plasma in the atmosphere according to an embodiment of the present invention includes a

plurality of dielectric panels, for example, four dielectric panels 13a, 13b, 13c, and 13d, a gas supply portion 14, power electrodes 15a, 15b, and 15c, ground electrodes 16a, 16b, 16c, and 16d, and a high frequency generator 17. The dielectric panels 13a, 13b, 13c, and 13d are vertically disposed at a  
5 predetermined interval in parallel to each other and fixed to the gas supply portion 14. The gas supply portion 14 supplies a gas to the space between dielectric panels 13a & 13b, 13b & 13c, and 13c & 13d. The power electrodes 15a, 15b, and 15c are linearly installed between dielectric panels 13a & 13b, 13b & 13c, and 13c & 13d, respectively, such as to be close to the gas supply portion  
10 14. The ground electrodes 16a, 16b, 16c, and 16d are formed in the ends of the dielectric panels 13a, 13b, 13c, and 13d, respectively. The high frequency generator 17 applies high frequency power to the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d.

The dielectric panels 13a, 13b, 13c, and 13d must have excellent  
15 insulating characteristics.

As described above, the gas supply portion 14 injects a gas into the space between dielectric panels 13a & 13b, 13b & 13c, and 13c & 13d. The gas may be various types of gases, such as, an inert gas (e.g., argon), oxygen, hydrogen, a compound gas, and the like.

20 The power electrodes 15a, 15b, and 15c are formed linearly, that is, in the form of wires, between dielectric panels 13a & 13b, 13b & 13c, and 13c & 13d, respectively.

The ground electrodes 16a, 16b, 16c, and 16d are formed in the ends of the dielectric panels 13a, 13b, 13c, and 13d, respectively. More specifically, the  
25 ground electrodes 16a, 16b, 16c, and 16d may be coated on the ends of the dielectric panels 13a, 13b, 13c, and 13d or inserted into the ends thereof.

The high frequency generator 17 applies high frequency power with a frequency of several to several hundreds of kHz to the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d. In this  
30 embodiment, power with a 32kHz frequency is applied thereto.

In this structure, when the high frequency generator 17 applies high frequency power to the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d, and the gas supply portion 4 applies a gas to

the space between dielectric panels 13a & 13b, 13b & 13c, and 13c & 13d, the gas turns into conductive plasma. The conductive plasma is injected from the ends of the dielectric panels 13a, 13b, 13c, and 13d to the outside.

At this time, a high voltage with a high frequency applied to the power electrodes 15a, 15b, and 15c flows along with the conductive plasma produced between the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d. In other words, an effect where a voltage formed in the power electrodes 15a, 15b, and 15c moves toward the ground electrodes 16a, 16b, 16c, and 16d appears. Also, a short plasma sheathing is formed on surfaces of the dielectric panels 13a, 13b, 13c, and 13d where the ground electrodes 16a, 16b, 16c, and 16d are located. Because plasma outside the plasma sheathing maintains a high voltage, neutral particles existing in the atmosphere in contact with the plasma sheathing turn into plasma due to the high voltage. As a result, plasma long in the direction of injection of a gas is obtained.

The plasma gas is not easily bound by an electric field between the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d.

Thus, the plasma gas injecting apparatus according to the present invention can inject a plasma gas farther than a conventional plasma injecting apparatus does.

Further, since a plurality of dielectric panels are disposed in parallel, power electrodes are formed at upper sides of the dielectric panels, and ground electrodes are formed on or in the ends of the dielectric panels, a greater amount of gas can turn into plasma.

As described above, a greater amount of plasma gas can be produced and injected farther than in a conventional technique, so that a to-be-processed object in a process such as an LCD manufacture, a PDP manufacture, a semiconductor manufacturing process, a PCB cleaning, a polymer surface modification, or the like, can be effectively cleaned in large quantities.

#### Industrial Applicability

As described above, in an atmospheric plasma injecting apparatus according to the present invention, power electrodes are formed at upper sides of dielectric panels, ground electrodes are formed on ends of the dielectric panels, and high frequency power is applied to the space between adjacent electrodes.

Hence, a gas applied to the space between adjacent dielectric panels can turn into plasma in the atmosphere. Since an electric field formed by the power electrodes and the ground electrodes is in the same direction as the direction of injection of the gas, the plasma gas can spout out farther than in the  
5 conventional technique.

What is claimed is:

1. An apparatus for injecting plasma in the atmosphere, the apparatus comprising:

a plurality of dielectric panels 13a, 13b, 13c, and 13d, which are disposed in parallel at predetermined intervals;

a gas supply portion 14, to which the dielectric panels 13a, 13b, 13c, and 13d are fixed and which supplies a gas to spaces between the dielectric panels 13a and 13b, between the dielectric panels 13b and 13c, and between the dielectric panels 13c and 13d;

power electrodes 15a, 15b, and 15c, which are linearly installed near the gas supply portion 14 and between the dielectric panels 13a and 13b, between the dielectric panels 13b and 13c, and between the dielectric panels 13c and 13d, respectively;

ground electrodes 16a, 16b, 16c, and 16d, which are formed in the ends of the dielectric panels 13a, 13b, 13c, and 13d, respectively; and

a high frequency generator 17, which applies high frequency power to the power electrodes 15a, 15b, and 15c and the ground electrodes 16a, 16b, 16c, and 16d.

1/2  
FIG.1 (PRIOR ART)

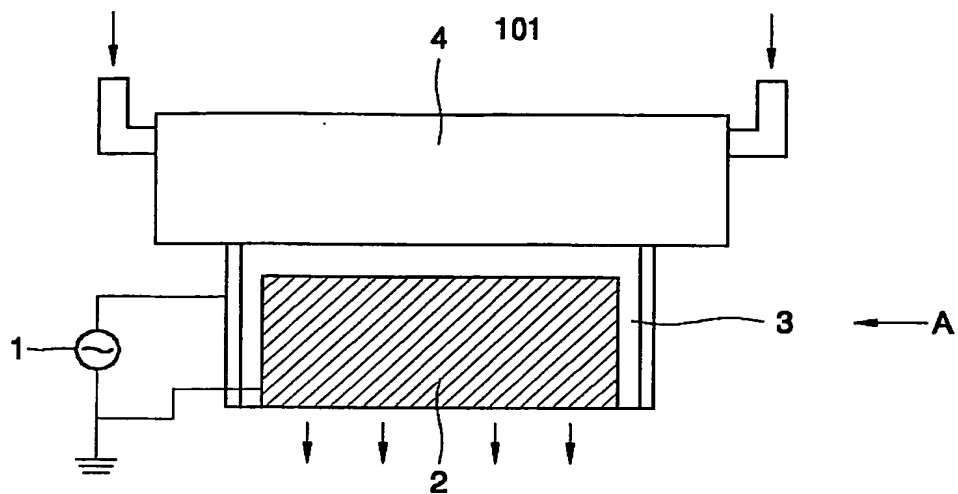
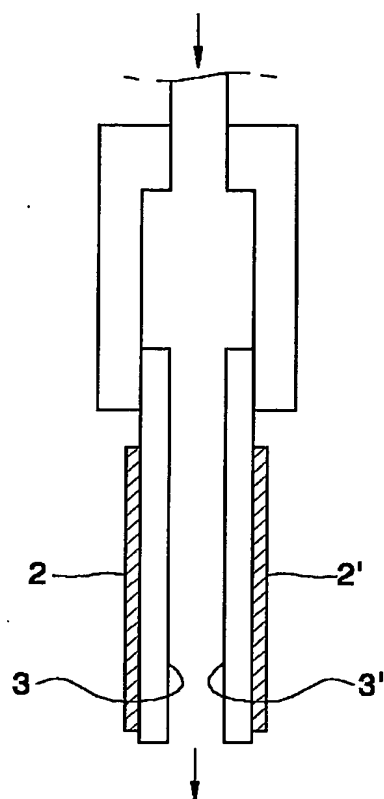


FIG.2



2/2  
FIG.3

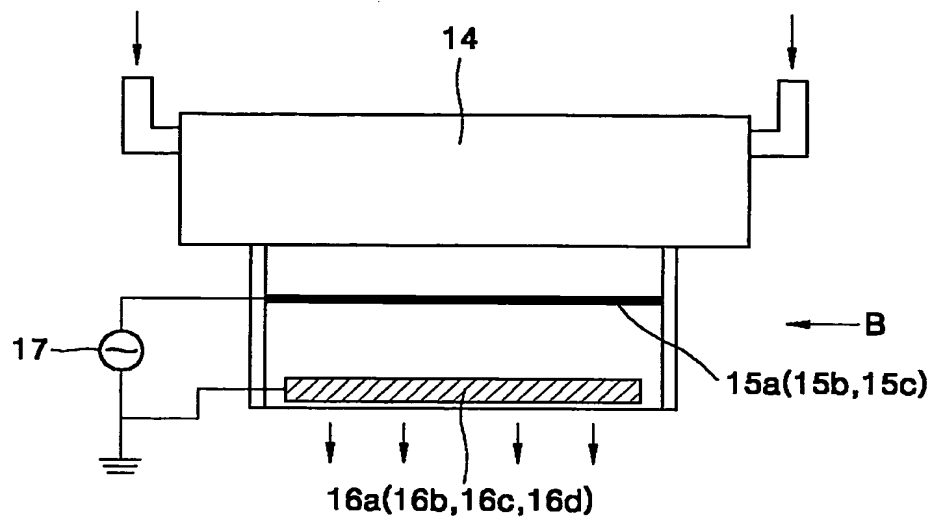
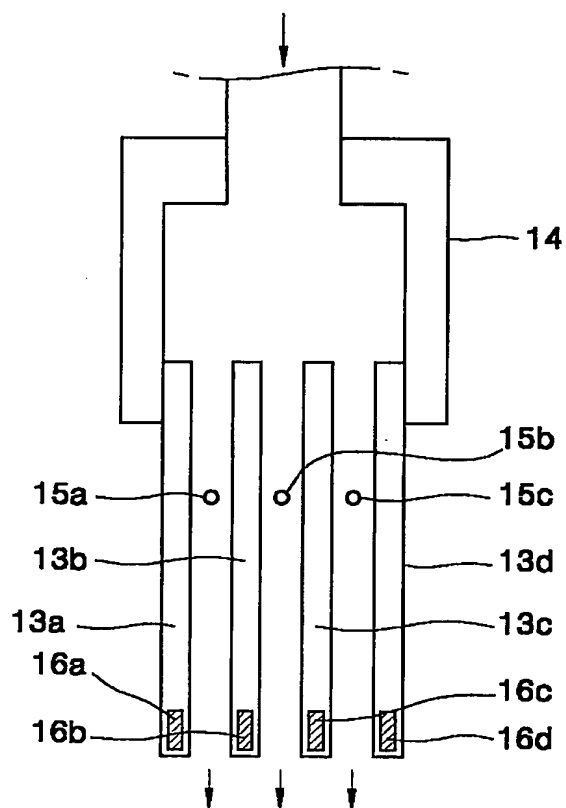


FIG.4



## INTERNATIONAL SEARCH REPORT

International application No.  
PCT/KR2004/000962

**A. CLASSIFICATION OF SUBJECT MATTER****IPC7 H05H 1/18**

According to International Patent Classification (IPC) or to both national classification and IPC

**B. FIELDS SEARCHED**

Minimum documentation searched (classification system followed by classification symbols)

IPC7 H05H

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Korean Patent and applications for inventions since 1975

Korean Utility model and applications for Utility models since 1975

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

eKJPAS, 'plasma', 'spray', 'jet', 'dielectric', 'nozzle'

**C. DOCUMENTS CONSIDERED TO BE RELEVANT**

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	KR 2001-60200 A (MATSUSHITA ELECTRIC WORKS, LTD.) 6 JULY 2001	1
A	US 6140773 A (UNIV CALIFORNIA, CRFILMS INC) 31 OCTOBER 2000	1

☐ Further documents are listed in the continuation of Box C.

☐ See patent family annex.

\* Special categories of cited documents:

"A" document defining the general state of the art which is not considered to be of particular relevance

"E" earlier application or patent but published on or after the international filing date

"L" document which may throw doubts on priority claim(s) or which is cited to establish the publication date of citation or other special reason (as specified)

"O" document referring to an oral disclosure, use, exhibition or other means

"P" document published prior to the international filing date but later than the priority date claimed

"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention

"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone

"Y" document of particular relevance; the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination being obvious to a person skilled in the art

"&amp;" document member of the same patent family

Date of the actual completion of the international search

31 MAY 2004 (31.05.2004)

Date of mailing of the international search report

31 MAY 2004 (31.05.2004)

Name and mailing address of the ISA/KR



Korean Intellectual Property Office  
920 Dunsan-dong, Seo-gu, Daejeon 302-701,  
Republic of Korea

Facsimile No. 82-42-472-7140

Authorized officer

LEE, Seung Joo

Telephone No. 82-42-481-8186

